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**PATENT APPLICATION**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Simon DELEONIBUS

Group Art Unit: 2826

Application No.: 10/591,863

Examiner:

Filed: September 6, 2006

Docket No.: 129344

For: FIELD EFFECT TRANSISTOR WITH SUITABLE SOURCE, DRAIN AND CHANNEL MATERIALS AND INTEGRATED CIRCUIT COMPRISING SAME

**APPLICANT'S SEPARATE RECORD OF PERSONAL INTERVIEW**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In reply to the February 28, 2008 personal interview, Applicant provides a separate record of the personal interview. Applicant also appreciates the courtesies extended by Examiners Kuo and Andujar to Applicant's representatives during the personal interview.

During the personal interview, Applicant's representatives traversed the rejections of claim 1 under 35 U.S.C. §102(e) over Orlowski (U.S. Publication No. 2006/0043498); claim 2 under 35 U.S.C. §103(a) over Orlowski in view of Ohata (U.S. Patent No. 4,556,895); and claims 1 and 2 under 35 U.S.C. §103(a) over Pfister (U.S. Patent No. 5,166,084) in view of Currie et al. (U.S. Patent No. 5,986,291) further in view of Valone (U.S. Patent No. 5,602,439).

As agreed during the personal interview, Orlowski is not prior art in view of National Stage Application of PCT/FR2005/000720 which in turn claims priority to French Application No. 043066 filed on March 25, 2004. A translation into English of French Application No. 043066 has been filed as requested by Examiner Kuo.

Further, as agreed during the personal interview, Pfister and Currie do not disclose or suggest that the source and drain materials, and electron affinities are different from each other and Pfister, Currie and Valone, individually or in combination, would not have disclosed or suggested a PMOS transistor in which the upper level of the valence band of the source material is lower than the channel material. Accordingly, the combination of Pfister, Currie and Valone would not have disclosed the features recited in claims 3-5.

It is respectfully requested that the rejection be withdrawn. In view of the foregoing, the February 14, 2008 Amendment and the translation into English of French Application No. 043066, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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JAO:MIL/hms

Date: March 14, 2008

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